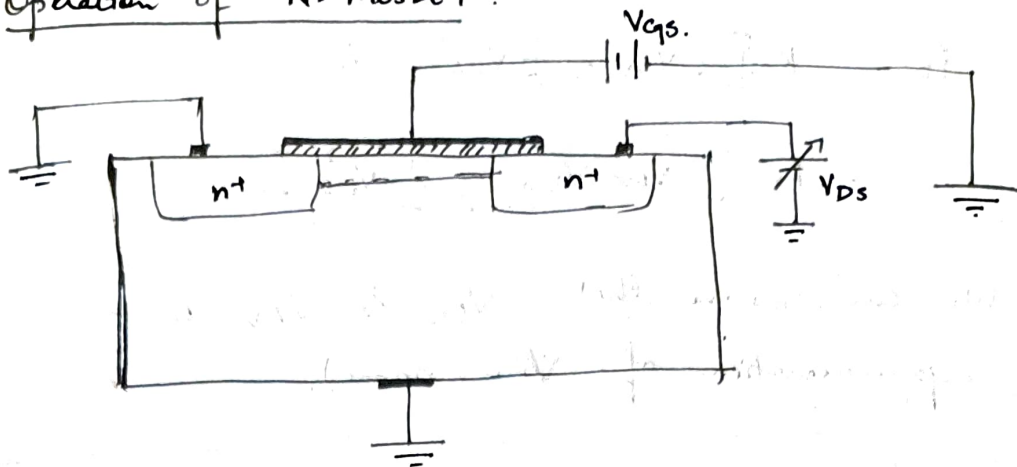


Operation of N-MOSFET:



(from prev week's notes).

When $V_{DS} \ll V_{ov} (V_{GS} - V_{th})$

$$I_{DS} = \left[\mu_n C_{ox} \left(\frac{W}{L} \right) V_{ov} \right] V_{DS}$$

→ $K_n = \mu_n C_{ox}$ [Process transconductance parameter]

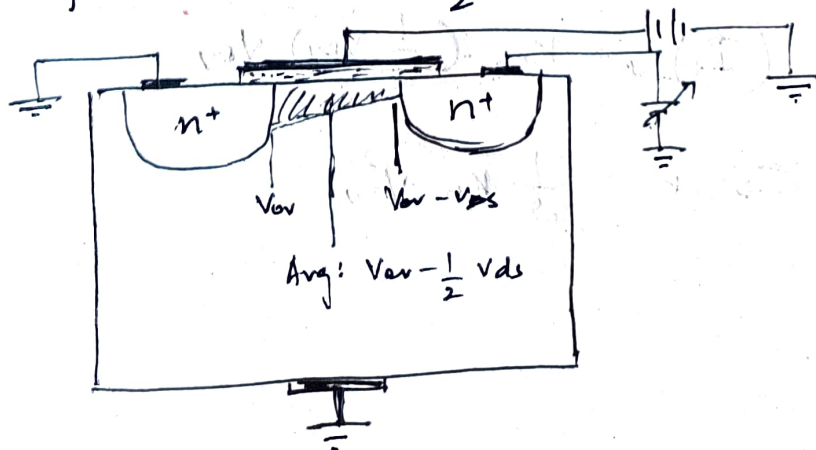
→ $\frac{W}{L}$ = Aspect ratio

→ $K_n = k_n' \left(\frac{W}{L} \right)$ = [Transistor transconductance parameter]

$$\Rightarrow I_{DS} = K_n (V_{GS} - V_{th}) V_{DS}$$

When $V_{DS} \ll V_{GS} - V_{th}$ [Smaller but significant].

The channel loses its uniformity. The potential at drain is $V_{ov} - V_{DS}$ and that on source is V_{ov} . The approximate voltage taken will be the mean of them = $V_{ov} - \frac{1}{2} V_{DS}$.

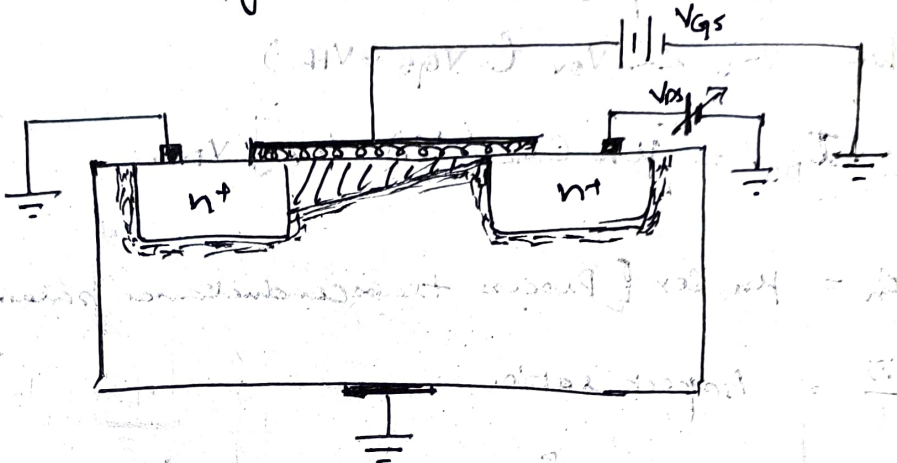


$$i_{DS} = k_n \left[(V_{ov} - \frac{1}{2} V_{DS}) \right] V_{DS}$$

$$= k_n \left[V_{ov} V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

(We can observe that $V_{DS} \ll V_{ov}$ is an approximation of the same).

When V_{DS} is greater than V_{ov} .



The channel enters a state of pinch-off, i.e., the channel is barely present on the die. Any excess voltage beyond the overdrive voltage will contribute to the formation of a depletion layer, causing the channel current to be saturated, as it is when $V_{DS} = V_{ov}$.

In this case

$$(I_{D})_{sat} = k_n \cdot \left(\frac{1}{2} V_{ov} \right) V_{ov}$$

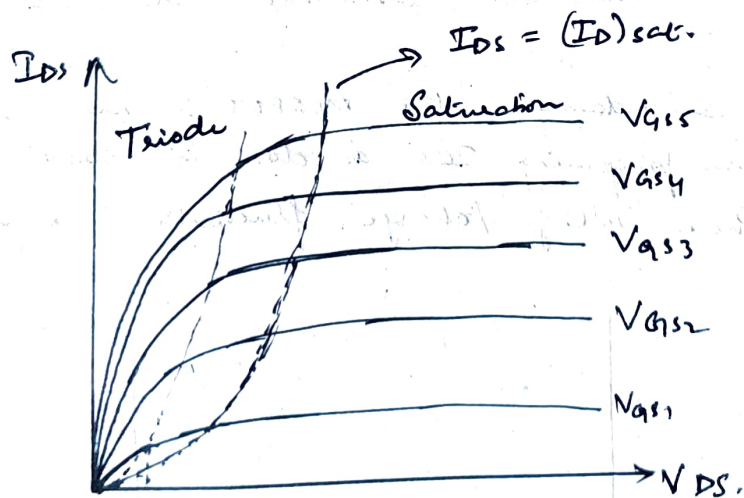
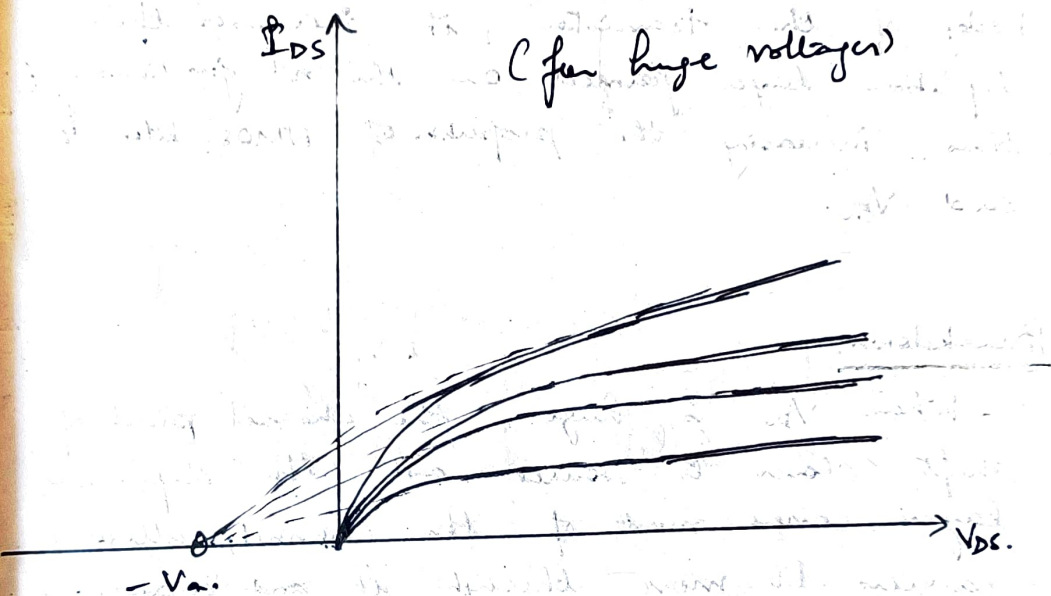
$$\Rightarrow (I_D)_{sat} = \frac{1}{2} k_n V_{ov}^2$$

Note:

When V_{DS} increases over a certain limit, the depletion layer provides carriers for current transfer, increasing the saturation current value.

$$I_{DS} = (I_D)_{sat} [1 + \lambda V_{DS}] \quad \lambda \propto \frac{1}{L}$$

When we plot the graphs for various V_{GS} , we can extend the linear slopes and find them meeting on the x-axis at $V = -V_a$ (Early voltage), just like the case with BJT.



Characteristic graph for N-MOS.

the three modes of a MOSFET are:

- Cut-off: $V_{GS} < V_{th}$
- Triode (linear): $V_{GS} > V_{th}$
 $V_{DS} \ll V_{GS} - V_{th}$
- Saturation: $V_{GS} > V_{th}$
 $V_{DS} \geq V_{GS} - V_{th}$

Body effect:

When a -ve voltage is applied on the body of the transistor, it increases the depletion layer formed on the n^+ junctions and thus, increasing the properties of NMOS like I_{DS} and V_{th} .

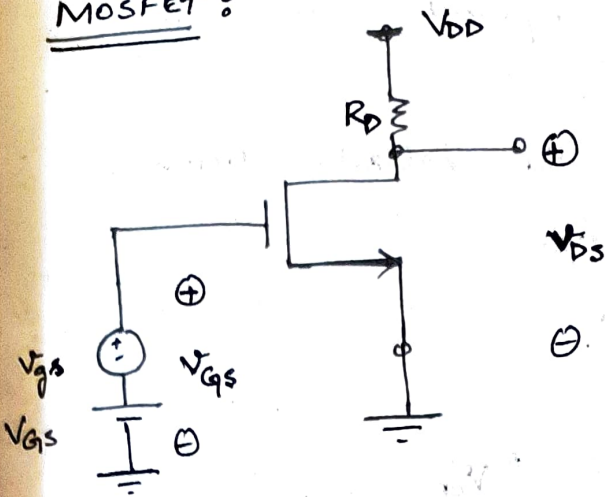
Breakdown:

When V_{DS} is huge, the channel pinch off shifts closer to source and the depletion layer covers most of the channel, allowing carriers to move through it ~~and carrying~~ causing an ~~overshoot~~ overshoot in current.

Note: This can damage the MOSFET in some cases. Hence, even preparing ICs is done in conditions ~~where~~ where voltage / charge fluctuation is very low.

Transistor Amplifier:

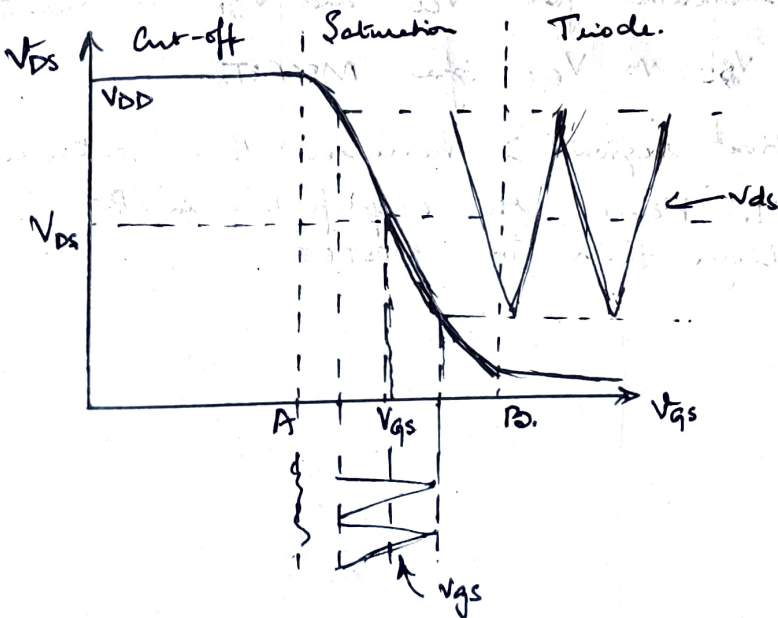
MOSFET:



Notation:

$$\underbrace{V_{DS}}_{\text{Mix of AC and DC}} = \underbrace{V_{DS}}_{\text{Purely DC}} + \underbrace{v_{ds}}_{\text{Purely AC.}}$$

Characteristic of a MOSFET (V_{DS} vs V_{GS}):



The MOSFET can be used as an amplifier in the saturation region, since the slope is linear in that region.

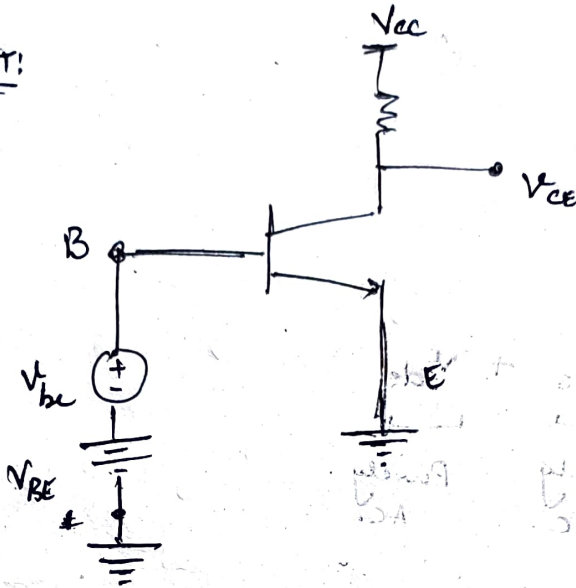
A DC voltage V_{GS} is applied on the gate, and a small DC voltage V_{DS} is observed.

A small AC voltage v_{gs} is then applied.

Note: When signal amplitude increases, the linearity ~~might~~ not remain intact.

Hence, the middle of the saturation region is generally chosen as V_{GS} .

BJT:

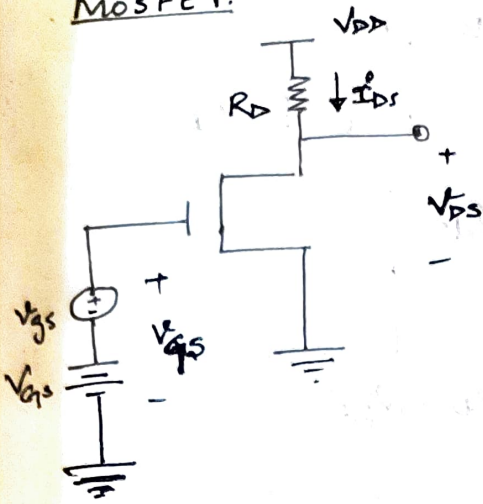


The characteristic for V_{ce} and V_{be} is similar to that of V_{GS} vs V_{DS} for MOSFETs.

The active region is narrower than saturation in BJT. Hence, the amplification in BJT is much larger than in MOSFET.

Gain for a small signal:

MOSFET:



$$I_{DS} = \frac{1}{2} k_n [V_{GS} - V_{th}]^2$$

$$V_{DS} = V_{DD} - I_{DS} R_D.$$

$$i_{DS} = \frac{1}{2} k_n [V_{GS} - V_{th}]^2$$

$$= \frac{1}{2} k_n [(V_{GS} - V_{th}) + v_{gs}]^2$$

$$= \frac{1}{2} k_n [(V_{GS} - V_{th})^2 + 2(V_{GS} - V_{th}) v_{gs} + v_{gs}^2]$$

When $v_{gs} \ll V_{GS} - V_{th}$, $v_{gs}^2 \ll$ rest term.

$$\approx \frac{1}{2} k_n (V_{GS} - V_{th})^2 + k_n (V_{GS} - V_{th}) v_{gs}$$

$$\approx I_{DS} + i_{ds}$$

$$\Rightarrow i_{ds} = k_n (V_{GS} - V_{th}) v_{gs} = g_m v_{gs}$$

$$\text{where } g_m = \frac{i_{ds}}{v_{gs}} = k_n (V_{GS} - V_{th}) = \frac{2 I_{DS}}{V_{GS} - V_{th}}$$

= Transconductance gain

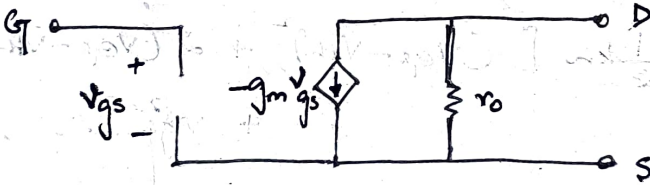
$$\begin{aligned}
 V_{DS} &= V_{DD} - i_{DS} R_D \\
 &= V_{DD} - [I_{DS} + i_{ds}] R_D \\
 &= (V_{DD} - I_{DS} R_D) + (-i_{ds} R_D) \\
 &\quad \downarrow \\
 &= V_{DS} + v_{ds}.
 \end{aligned}$$

$$\begin{aligned}
 \Rightarrow v_{ds} &= -i_{ds} R_D \\
 &= -\cancel{I_{DS}} g_m R_D \cdot v_{gs}.
 \end{aligned}$$

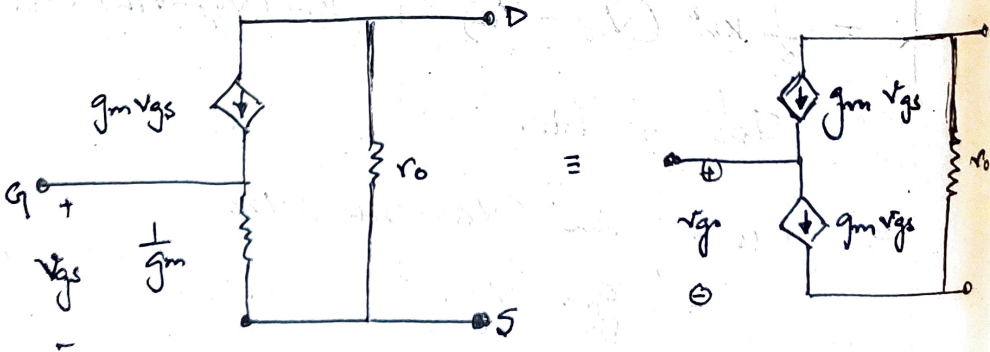
$$\Rightarrow \frac{v_{ds}}{v_{gs}} = -g_m R_D.$$

Small signal equivalent model:

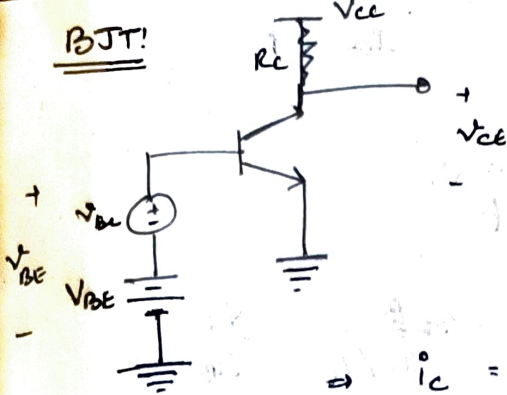
π - Model:



T - Model:



BJT!



$$I_C = I_S \cdot e^{\frac{V_{BE}}{V_T}}$$

$$V_{CE} = V_{CC} - I_C \cdot R_C$$

$$V_{BE} = V_{BE} + V_{BC}$$

$$\Rightarrow i_c = I_S \cdot e^{\frac{V_{BE} + V_{BC}}{V_T}} = I_S e^{\frac{V_{BE}}{V_T}}$$

$$= [I_S e^{\frac{V_{BE}}{V_T}}] (e^{\frac{V_{BC}}{V_T}})$$

$$\left[\text{for } V_{BC} \ll V_T, e^{\frac{V_{BC}}{V_T}} \approx 1 + \frac{V_{BC}}{V_T} \right]$$

$$i_c = I_C \left(1 + \frac{V_{BC}}{V_T} \right)$$

$$\Rightarrow i_c = I_C + \frac{I_C}{V_T} V_{BC} = I_C + i_c$$

$$\Rightarrow i_c = \frac{I_C}{V_T} V_{BC} = g_m V_{BC}$$

$$\Rightarrow g_m = \frac{i_c}{V_{BC}} = \frac{I_C}{V_T}$$

$$V_{CE} = V_{CC} - i_c \cdot R_C$$

$$= V_{CC} - I_C R_C - i_c R_C$$

$$= V_{CE} + v_{ce}$$

$$\Rightarrow v_{ce} = -g_m R_C \cdot v_{be}$$

$$\Rightarrow \frac{v_{ce}}{v_{be}} = -g_m R_C$$

$$i_B = \frac{i_C}{\beta} = \frac{I_C + i_c}{\beta} = I_B + i_b$$

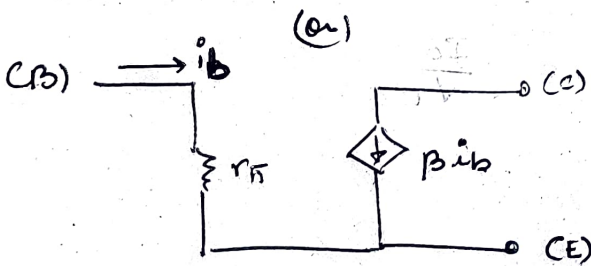
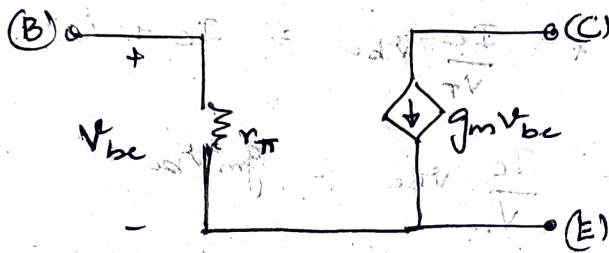
$$\Rightarrow i_b = \frac{i_c}{\beta} = \frac{g_m}{\beta} v_{be}$$

$$\Rightarrow r_{\pi} = \frac{v_{be}}{i_b} = \frac{\beta}{g_m} = \frac{\beta}{I_C/V_T} = \frac{V_T}{I_B}$$

Illy, $r_e = \frac{v_{be}}{i_c} = \frac{1}{g_m} = \frac{V_T}{I_E}$

Equivalent model:

π -Model:



T-Model:

